



Self-focused ion beam lithography using dielectric lens

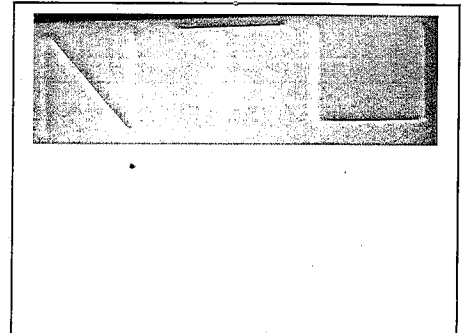
PI : Prof. Miin-Jang Chen
Department of Materials Science and Engineering,
National Taiwan U.

Experience:

http://www.mse.ntu.edu.tw/index.php?option=com_zoo&task=item&item_id=47&Itemid=902&lang=tw

Market Needs:

Future nano technology requires next generation sub-5 nm lithography



Our Technology:

Fabrication of large area sub-5nm nano patterns

Strength:

Resolve the resolution problems of the conventional lithography in regard to sub-5nm lithography.

Competing Products:

EUV, He ion lithography

Intellectual Properties:

USA

Filing to PTO; filing date 9/14/2015 and accorded No 14/852,818

Contact (do not need to fill out):

Center for Industry-Academia Cooperation, NTU
Tel: 02-3366-9945, E-mail: ntuciac@ntu.edu.tw

This information herein is intended for potential license of NTU technology only. Other usage of all or portion of this information in whatever form or means is strictly prohibited. Kindly contact us and we will help to achieve your goal the best we can.